

In the Claims:

Please amend the claims as follows:

1-22 (cancelled)

23. (new) A method for the preparation of doped oxide material, the method comprising:

bringing substantially all reactants into a vaporous form in a gas phase by heating the reactants;

mixing the reactants together to create a gas flow; and

bringing the gas flow at a sufficiently high temperature in to a contact with at least one oxidant in order to form particles comprising an oxide material in a reaction so that all the components of the reactants reach a supersaturated state substantially simultaneously and there is no time in the reaction to reach a chemical phase equilibrium.

24. (new) The method according to claim 23, wherein said oxide material is doped glass material, which is formed of the base materials and dopants of glass material by bringing these to react with each other in the gas phase in a vaporous form in order to form glass particles.

25. (new) The method according to claim 23, wherein agglomeration of the oxides is performed by fast oxidation of reactants into oxide particles.

26. (new) The method according to claim 25, wherein said fast oxidation of reactants is achieved by directing one or more jets of oxidative gases to the gas flow of the reactants, preferably jets formed of oxygen and/or carbon dioxide.

27. (new) The method according to claim 26, wherein said one or more jets of oxidative gases are directed to the gas flow in a manner causing strong turbulence and mixing.

28. (new) The method according to claim 26, wherein the formation of oxide particles is intensified by directing said one or more jets of oxidative gases to the gas flow of reactants as colder than said gas flow.

29. (new) The method according to claim 23, wherein the fast oxidation of reactants into oxide particles is achieved and/or it is intensified by expanding the gas flow of reactants adiabatically.

30. (new) The method according to claim 29, wherein the gas flow of reactants is directed through the Lavall nozzle or the like.

31. (new) The method according to claim 23, wherein said oxide material is glass material, as whose base material is used inorganic or organic compound of silicon or germanium.

32. (new) The method according to claim 31, wherein the glass material comprises silicon tetrachloride or germanium tetrachloride, TEOS (tetraethylortosilicate), or GEOS

(tetraethoxygermanium).

33. (new) The method according to claim 23, wherein said oxide material is glass material, as whose dopant is used erbium, neodymium, other rare earth metal, aluminium, phosphorus, borium and/or fluorine.

34. (new) The method according to claim 23, wherein the oxide particles are formed in a reactor in which the temperature is approximately in a range between 1000 and 2000°C.